IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

In re Patent Application of

Kazuya KAMON

Application No.: 09/320,946

Filed: May 26, 1999

For: PHOTOMASK, FABRICATION

METHOD OF PHOTOMASK, AND FABRICATION METHOD OF SEMICONDUCTOR INTEGRATED

CIRCUIT

SEP 2 2 2000 (2)

Examiner: S. Mohamedulla

AMENDMENT UNDER 37 C.F.R. § 1.111

Assistant Commissioner for Patents Washington, D.C. 20231

Sir:

This amendment responds to the Office Action dated May 24, 2000 (Paper No. 4).

Concurrently filed with this Amendment are abstracts of the references cited in the

Information Disclosure Statement. Please amend the above-noted application as follows:

IN THE CLAIMS:

Please amend claims 2-15 and 20 and add new claims 27 and 28 as follows:

Claim 2, line 3/change "said" to --a--;

line 6, change "flat" to --planarized--.

3. (Amended) A photomask according to claim 2, wherein an end section of said phase shift pattern that is contacted to said transparent substrate has a sloped shape that gradually decreases, the sloped shape formed by chemical and mechanical polishing.

